**Electronic Supplementary Information** 

## **Bulk Charge-Transfer Doping of Amorphous Metal Oxide: Fullerene Blends for Solution-Processed Amorphous Indium Zinc Oxide Thin-Film Transistors**

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**Table S1.** Summary of the energy level values for C60-MA

Method	$E_{g}(eV)$	HOMO (eV)	LUMO (eV)
DFT <sup>a)</sup>	2.60	-5.88	-3.28
CV <sup>a)</sup>	2.22	-5.87	-3.65

<sup>a)</sup> Values from density functional theory (DFT) calculations are taken from ref. 1; <sup>b)</sup> Values from cyclic voltammetry (CV) study presented in **Figure S1**.

The CV value is evaluated by these equations:

HOMO(eV)= - 4.8 -  $(E_{onset,Ox} - E_{1/2, ferr})$ LUMO(eV) = - 4.8 -  $(E_{onset,Red} - E_{1/2, ferr})$ 

Where  $E_{1/2, ferr} = (E_{onset, Ox, ferr} + E_{onset, Red, ferr})/2$ 

x (wt%) <sup>a)</sup>	E <sub>G</sub> (eV)	$\frac{\Delta E_{VRM}^{F}}{(eV)}$	Ecut-off (eV)	VBM (eV)	Fermi level (eV)	CBM (eV)	
0.0	3.68	-3.29	-16.85	-7.66	-4.37	-3.98	
0.5	3.70	-3.47	-17.00	-7.69	-4.21	-3.99	
1.0	3.71	-3.47	-17.16	-7.53	-4.06	-3.83	
1.5	3.70	-3.58	-17.29	-7.51	-3.93	-3.81	
2.0	3.71	-3.58	-17.16	-7.63	-4.06	-3.92	
C60-MA concentration (wt%)							

**Table S2.** Summary of the energy levels obtained for *a*-IZO:*x*% C60-MA composites from UPS and optical spectroscopy measurement



**Figure S1.** Cyclic voltammetry (CV) curve of C60-MA (inset shows the CV curve for ferrocene in 2-methoxyethanol).



**Figure S2.** Cross-section transmission electron microscopy (TEM) image of 1% doped a-IZO composite film with different scales of 200 nm (a), 50 nm (b), 20 nm. The inset in (c) is selected area electron diffraction (SAED) pattern.



**Figure S3.** X-ray photoelectron spectra of O1s (a) and C1s (b) levels of *a*-IZO:x% C60-MA composites for x = 0.0%, 1.0%, 2% and 4% without surface sputtering.



Figure S4. O1s XPS peak ratio analysis for the composite films with surface sputtering.



**Figure S5.** X-ray photoelectron spectra of O1s (a) and C1s (b) levels of *a*-IZO:x% C60-MA composites for x = 0.0%, 1.0%, 2% and 4% with surface sputtering.



**Figure S6.** C1*s* XPS spectra of C60-MA. (a-b) C1s peak analysis of as spun C60-MA C1s without sputtering (a), with sputtering and C60-MA (b). (c-d) C1s peak analysis of 250oC annealed C60-MA without sputtering (c) and with sputtering (d).



**Figure S7.** XPS peak ratio analysis of *a*-IZO:x% C60-MA composites for x = 0.0%, 1.0%, 2% and 4% with surface sputtering. (a) The aromatic C to carbonyl C ratio and (b) the C1s to In content ratio of *a*-IZO:x% C60-MA composites for x = 0.0%, 1.0%, 2% and 4% with surface sputtering.



**Figure S8.** ATR-FTIR data of a-IZO:x% C60-MA composite films (repeated 20 times spin-coating), pristine C60-MA powder and dried mix precursor solution on native silicon substrate. (a) Whole range ATR-FTIR spectra of a-IZO:x% C60-MA composite films, and precursors. (b) Enlarged ATR-FTIR spectra of a-IZO:x% C60-MA composite films.



Figure S9. Ultraviolet photoemission spectra of *a*-IZO:*x*% C60-MA composites.



Figure S10. Analysis of the ultraviolet photoemission spectra of *a*-IZO:*x*% C60-MA composites.



**Figure S11.** Field emission scanning electron microscopy (FESEM) image of *a*-IZO:x% C60-MA composites for x = 0.0% (a), 1.0% (b), 2.0% (c) and 4.0% (d) with 1 µm scale. The insets are 100 nm scale.



**Figure S12.** a) Energy Dispersion X-ray Spectroscopy (EDS) image of a-IZO:4% C60-MA and b) atomic % of selected point in EDS image



**Figure S13.** Representative thin-film transistor transfer characteristics of *a*-IZO:*x*% C60-MA composites.



**Figure S14.** Representative thin-film transistor output characteristics of *a*-IZO:*x*% C60-MA composites.



**Figure S15.** Positive bias stress test results for TFTs of *a*-IZO:*x*% C60-MA composites for x = 0.0% (a), 0.5% (b), 1.0% (c) and 1.5% (d) with V<sub>G</sub> = 50 V and V<sub>DS</sub> = 25 V.

## References

1. B. D. Joshi, A. Srivastava, P. Tandon and S. Jain, *Spectrochimica Acta Part A: Molecular and Biomolecular Spectroscopy*, 2011, **82**, 270-278.